



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :
Tuqiang NI et al :
Serial No. 09 689,616 : Group Art Unit: 1763
Filed: October 13, 2000 : Examiner: L. Alejandro
For: VACUUM PLASMA PROCESSOR HAVING A CHAMBER WITH ELECTRODES
AND A COIL FOR PLASMA EXCITATION AND METHOD OF OPERATING
SAME

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
Washington, D.C. 20231

Dear Sir:

In response to the December 18, 2002 non-final Office Action, please amend the application as follows:

IN THE CLAIMS:

Please add claims 40-44:

--40. The vacuum plasma processor of claim 7 further including a power supply arrangement for supplying RF ion energization to the coil and the workpiece and for supplying (a) voltages to the semiconductor member and the non-magnetic metal arrangement and (b) a reference voltage to a metal wall of the chamber.

--41. The vacuum plasma processor of claim 40 wherein the power supply arrangement is arranged for supplying the reference voltage to the semiconductor member.

--42. The vacuum plasma processor of claim 41 wherein the power supply arrangement is arranged for supplying the reference voltage to the non-magnetic metal arrangement.